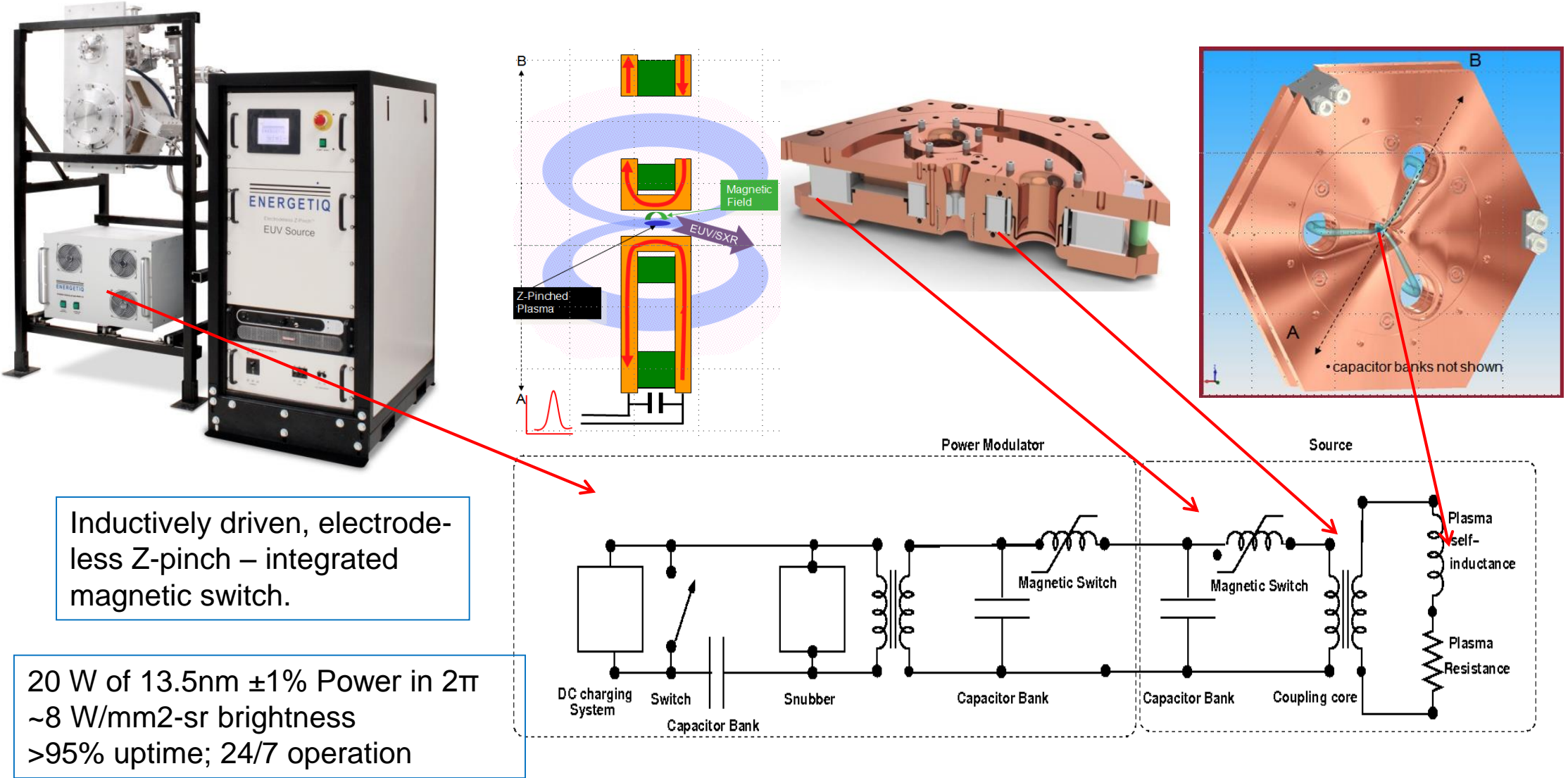
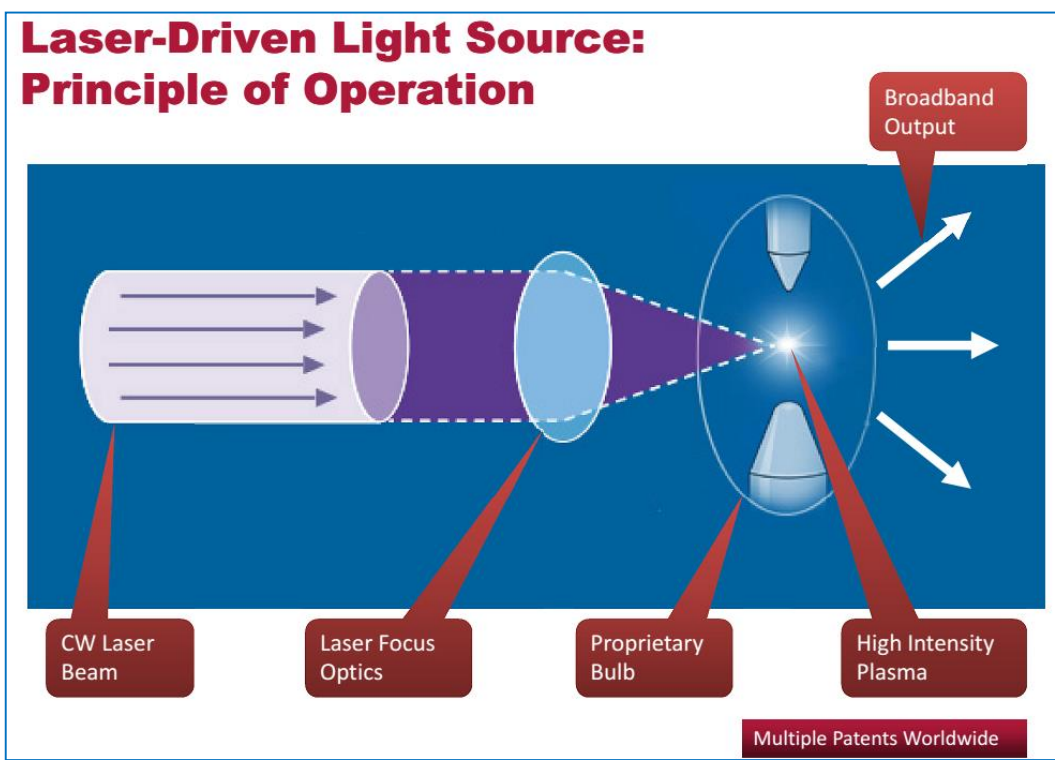


Energetiq Technology Inc. produces a variety of light sources. This poster will review the physics of these products (and some proposed devices), with an emphasis on applications. The technology to be described includes the basic EQ-10 at 13 nm wavelength, and related devices including higher power, high pulse rate, and proposed high brightness concepts, and the 2.88 nm source for water window microscopy derived from the EQ-10. In addition, we will present a summary of the physics and applications of the family of products based on Energetiq's Laser Driven Light Source technology.

Electrode-less Z-Pinch™

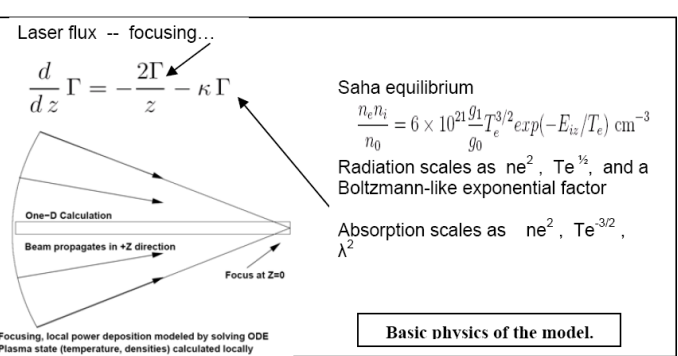
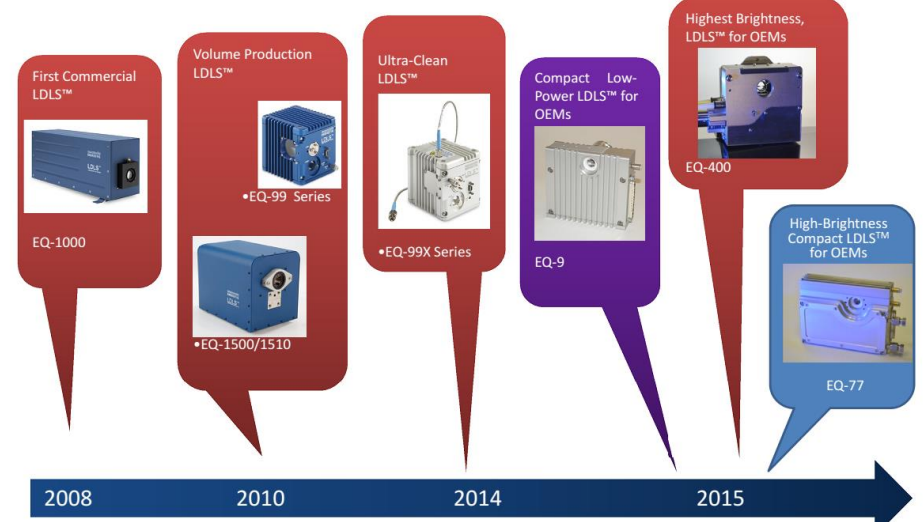


Vis/UV Light Sources - LDLS™



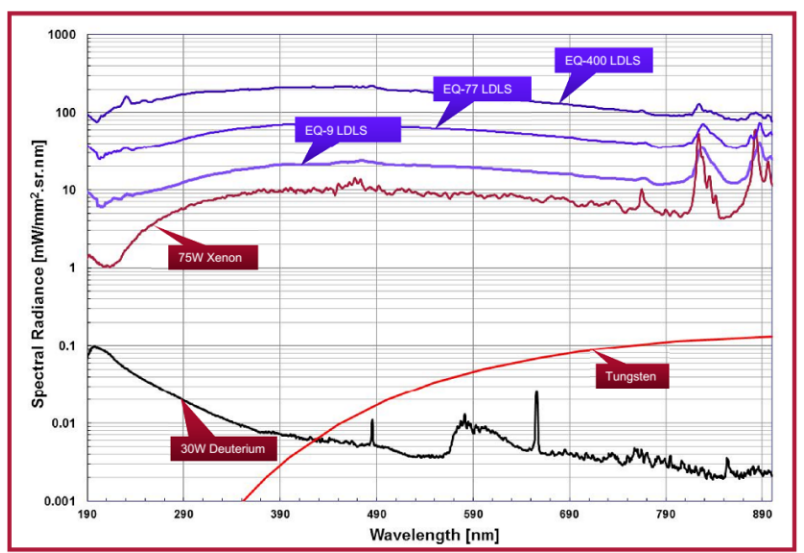
Spectral brightness scales with laser power (unlike arc lamp, where plasma increases in size, limiting brightness).

LDLS™ History of Innovation



Applications

- Analytical Spectroscopy
- HPLC, AA, UV-Vis
- Materials Characterization
- Environmental Analysis
- Hyperspectral Imaging
- Gas Phase Measurements
- Advanced Microscopes
- Endoscopes...

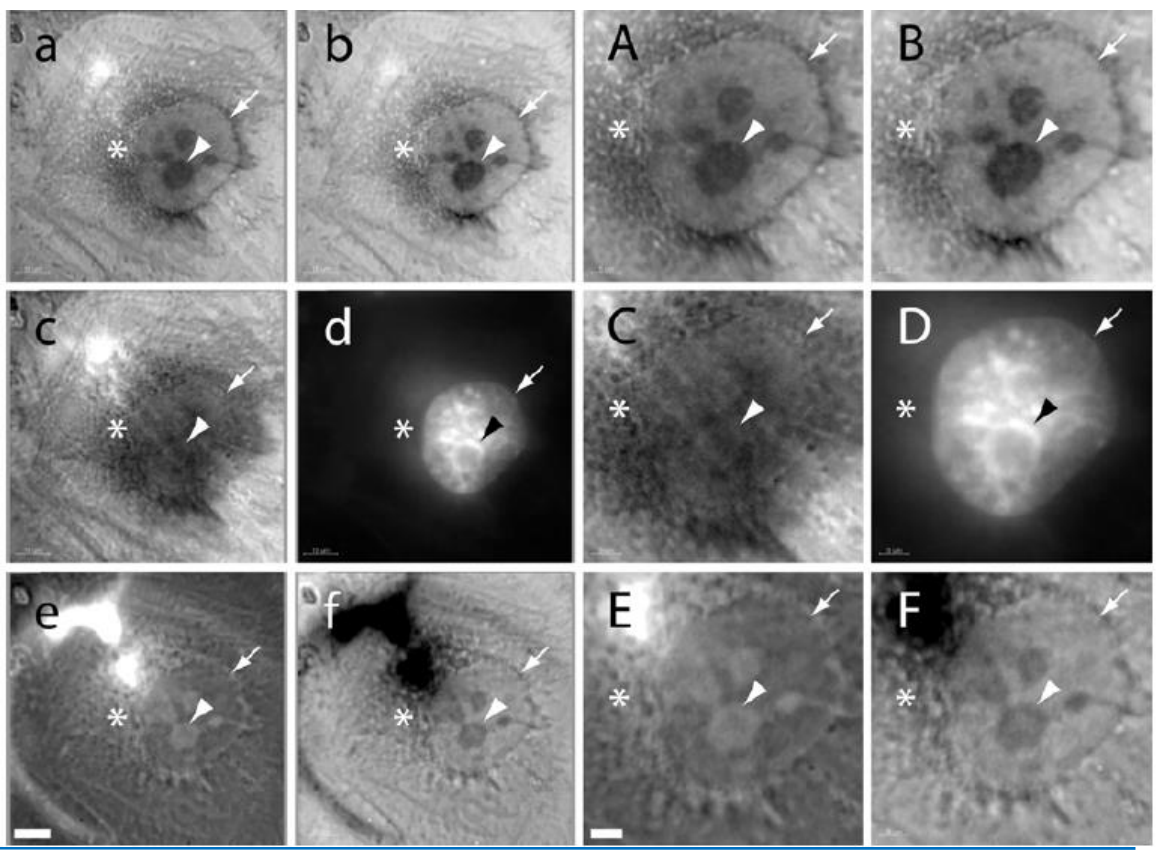
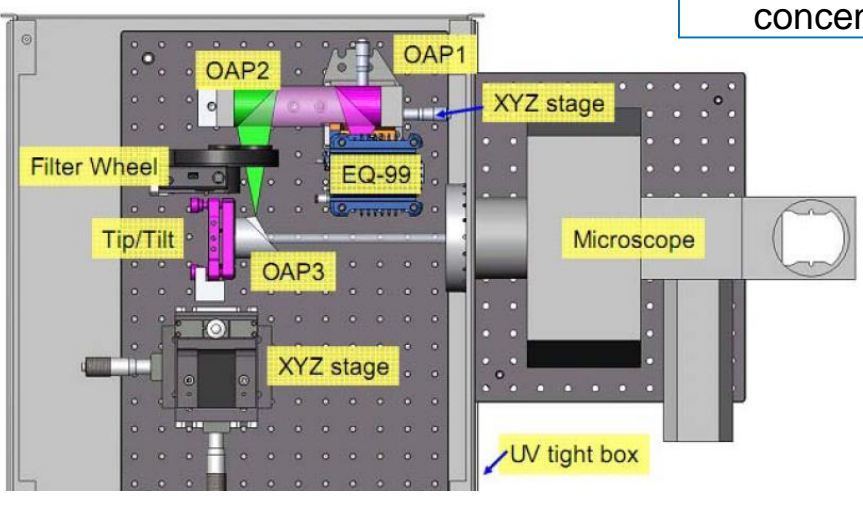


Application – UV Microscopy

250x improvement in exposure times compared to UV LED. Allows direct mapping of protein concentrations.[11]



Applications and Installations ~ 25 worldwide



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Advanced Concepts[8]

